

# First-principles investigation of the mechanism of oxidation in atomic layered MoS<sub>2</sub> structures

Junga Ryou<sup>1</sup>

Han Seul Kim<sup>2</sup>, Juho Lee<sup>3</sup>, and Yong-Hoon Kim<sup>1,3</sup>

<sup>1</sup> Graduate School of Energy, Environment, Water, and Sustainability, Korea Advanced Institute of Science and Technology (KAIST), 291 Daehak-ro, Yuseong-gu, Daejeon 34141, Korea

<sup>2</sup> Center for Division of National Supercomputing Research and Development, Korea Institute of Science and Technology Information (KISTI), 245 Daehak-ro, Yuseong-gu, Daejeon 34141, Korea

<sup>3</sup> School of Electrical Engineering, Korea Advanced Institute of Science and Technology (KAIST), 291 Daehak-ro, Yuseong-gu, Daejeon, 34141, Korea

[y.h.kim@kaist.ac.kr](mailto:y.h.kim@kaist.ac.kr)

## Abstract

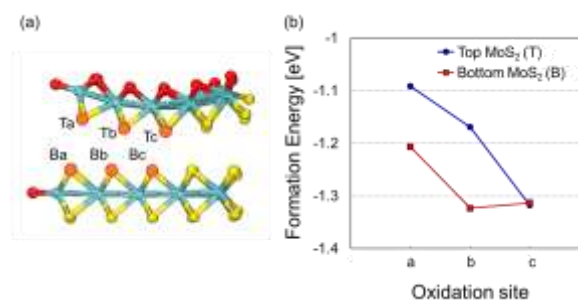
Two-dimensional transition metal dichalcogenides (TMDCs) has attracted a great deal of attention due to its unique properties. For electronic and optoelectronic device applications of TMDCs, the oxidation mechanisms studies are important. Herein, we investigate the oxidation mechanisms of MoS<sub>2</sub> layer carrying out density functional theory (DFT) calculations. We analyze the atomic and electronic properties of oxidized MoS<sub>2</sub> layer structures. We find that the first step of the oxidation process occurs at the edge and top basal plane of MoS<sub>2</sub>. The MoS<sub>2</sub> nanocluster has a bending structure after fully oxidation of top basal plane. We suggest that the bending and opening of edges is the key step that allows the self-limiting layer-by-layer oxidation of multilayer MoS<sub>2</sub>. The opened edge atomic structures of MoS<sub>2</sub> nanocluster make enough space to insert the oxygen atom at the interface of bilayer MoS<sub>2</sub>. We will also consider the diffusion pathway of oxygen atoms into interface and calculate the stable structures of oxidation on the two sides of bilayer MoS<sub>2</sub>. The accumulated understanding of oxidation mechanisms can be applied to achieve the refined control of TMDCs

oxidation processes, which will allow the synthesis of atomically precise MoS<sub>2</sub>-MoO<sub>3</sub> heterostructures and the prevention of MoS<sub>2</sub> oxidation under ambient and oxidative conditions. Based on these result, we provides the basic understanding on the oxidation mechanism of TMDCs materials.

## References

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## Figures



**Figure 1:** (a) An atomistic model of the oxidized zigzag MoS<sub>2</sub> nanoribbon (b) Oxidation energies of a, b, and c sites for T and B.